

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	34	(overlying or top or deposit or deposited or depositing or sputter or sputtering or sputtered or grow or grew or growing) near8 (organic near molecules).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/22 10:29
L3	34	((overlying or top or deposit or deposited or depositing or sputter or sputtering or sputtered or grow or grew or growing) near8 (organic near molecules)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/22 10:17
L4	257	(overlying or top or deposit or deposited or depositing or sputter or sputtering or sputtered or grow or grew or growing) near8 (organic near molecules)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/22 10:17
L5	5846515	(residue or residual or (left near over) or left-over or remainder or excess or remains or remaining or portion)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/22 10:18
L6	11	(4 and 5).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/22 10:18
L7	5	(overlay or overlaid or overlaying) same ((organic near molecules) or molecule) same ion same (substrate or wafer) same structure	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/22 10:23
L8	1261	(overlay or overlaid or overlaying) same ((organic near molecules) or molecule)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/22 10:23
L9	1031699	(remove or removed or removing) same (residue or residual or remaining or remains or leftover or left-over or remainder)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/22 10:25
L10	536	8 and 9	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/22 10:24

L12	1012	8 and (residue or residual or remaining or remains or leftover or left-over or remainder)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/22 10:25
L13	9	(8 and (residue or residual or remaining or remains or leftover or left-over or remainder)).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/22 10:26
L14	11	((remove or removing or removed) same (organic near molecule) same (residue or residual or remains or remainder or remaining)).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/22 10:28
L15	0	((apply or applying or applied) same (ion near solution) same (organic near molecule)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/22 10:31
L16	483	((deposit or depositing or deposited) near8 (layer or metal) same ((organic near molecule) or molecular)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/22 10:33
L17	6821	((deposit or depositing or deposited) near8 (layer or metal) same ((organic near molecule) or molecular))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/22 10:33
L18	244	17 and (metal near ion)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/22 10:34
L19	4	(17 and (metal near ion)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2005/11/22 10:34